

MgO:LiNbO3 Crystals for EO applications

- Preferably for Er:YAG-, Ho:YAG-, Tm:YAG laser
- Wavelengths up to 3µm
- Higher damaging threshold than non-doping LiNbO3
- Brewster for laser with low amplification

MgO:LiNbO3 crystals have become one of the most commonly used material for Q-switches and phase modulators for its high EO coefficients, MgO:LiNbO3 has a higher damaging threshold than the non-doping LiNbO3 crystals. With an electric field applied transverse to the direction of light propagation, LiNBO3 cells can be configured to operate at a lower voltage than comparable KD*P cells. LiNbO3 can also be a good choice for infrared wavelengths as long as 3.0 µm. Hangzhou Shalom EO offers the polished, and AR coating and Au-Cr electroded MgO:**LiNbO3 crystals** used in pockels cells.





Modules or types

A variety types of crystals are available upon your request:

- Crystal boules with inspection polishing
- Crystal blanks with inspection polishing
- Crystals with laser grade polishing
- Crystals with AR coating and Cr-Au electrode



SPECIFICATIONS

Specification of MgO:LiNbO3 crystals for pockels cells applications			
Crystal materials	MgO(5mol%):LiNbO3 crystals		
Size	Customized		
Size tolerance	+/-0.1mm		
Length tolerance	+/-0.2mm		
Surface quality	20/10 S/D		
Parallelism	<20 arc seconds		
Flatness	< Lambda/10 @633nm		
Chamfer	0.1-0.3mmx45°		
Chips	<0.15mm		
Side surface	Fine ground		
Orientation tolerance	< 10 arc minutes		
Wavefront distortion	<lambda 4@633nm<="" td=""></lambda>		
Extinction ratio	>200:1		
Coating	AR/AR@1064nm or customized		
Damaging threshold	>300mW/cm^2@1064nm 10nS 10Hz pulse		
Electrode on side surface	Chrome gold electrode (Cr+Au)		

Note: crystals with other special specificaton is available upon request

Example: MgO:LN crystals with bruster angle



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Basic Properties

Basic Properties			
Crystal Structure		Trigonal, space group R3c	
Cell Parameters		a = 0.515, c = 13.863, Z = 6	
Melting Point		1255±5oC	
Curie Point		1140±5oC	
Mohs Hardness		5	
Density		4.64 g/cm3	
Absorption Coefficient		~ 0.1%/cm @ 1064 nm	
Solubility		insoluble in H2O	
Relative Dielectric Consta	nt	e ^T ₁₁ /e ₀ : 85 e ^T ₃₃ /e ₀ : 29.5	
Thermal Expansion Coefficien 25oC)	ts(@	a, 2.0 x 10⁻⁶/K c, 2.2 x 10⁻⁶/K	
Thermal Conductivity		38 W /m /K @ 25oC	
Linear Optical Properties			
Transparency Range		420-5200nm	
		ne=2.146, no = 2.220 @ 1300 nm	
Refractive Indices		ne= 2.156, no = 2.232 @ 1064 nm	
		ne= 2.203, no = 2.286 @ 632.8nm	
Optical Homogeneity		~ 5 x 10 ⁻⁵ /cm	
Sellmeier Equations	ı	1^{2} o (I) = 4.9048+0.11768/(I ² - 0.04750) - 0.0271	1691 ²
(l in mm)	n	$^{2}e(I) = 4.5820 + 0.099169/(I^{2} - 0.04443) - 0.021$	950l ²
Nonlinear Optical Properties			
NLO Coefficients		d33 = 34.4 pm/V	
		d31 = d15 = 5.95 pm/V	
		d22 = 3.07 pm/V	
Efficiency NLO Coefficients		deff =5.7 pm/V or ~14.6 x d36 (KDP)	
		for frequency doubling 1300 nm	
	'S	deff =5.3 pm/V or \sim 13.6 x d ₃₆ (KDP)	
	.0	for OPO pumped at 1064 nm	
	deff =17.6 pm/V or \sim 45 x d ₃₆ (KDP)		
		for quasi-phase-matched structure	
Electro-Optic Coefficients		g'33 = 32 pm/V, g ^s 33 = 31 pm/V	
		g'31 = 10 pm/V, g ^s 31=8.6 pm/V	
		g ¹ 22 = 6.8 pm/V, g ⁵ 22= 3.4 pm/V	
Half-Wave Voltage, DC		3.03 KV	
Electrical field z, light ^z		4.02 KV	
Electrical field x or y, light z			

